

# Different Functional Nanostructures Self-Assembled Selectively on Inert Substrates

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# Nanostructural Self-assembly

- Nanostructures form themselves under thermodynamic/kinetic driving forces; **parallel processes and no masks needed**
- **Metastable structures**, hopefully with novel properties
- Examples: CNTs, nanowires, quantum dots, nanopatterns...
- **The remaining problems:** precise control of size, shape, type and location of nanostructures
- **Understanding of growth mechanism:** effects of kinetics, surfaces, thermodynamics and mechanics

# Functional Nanostructural Materials

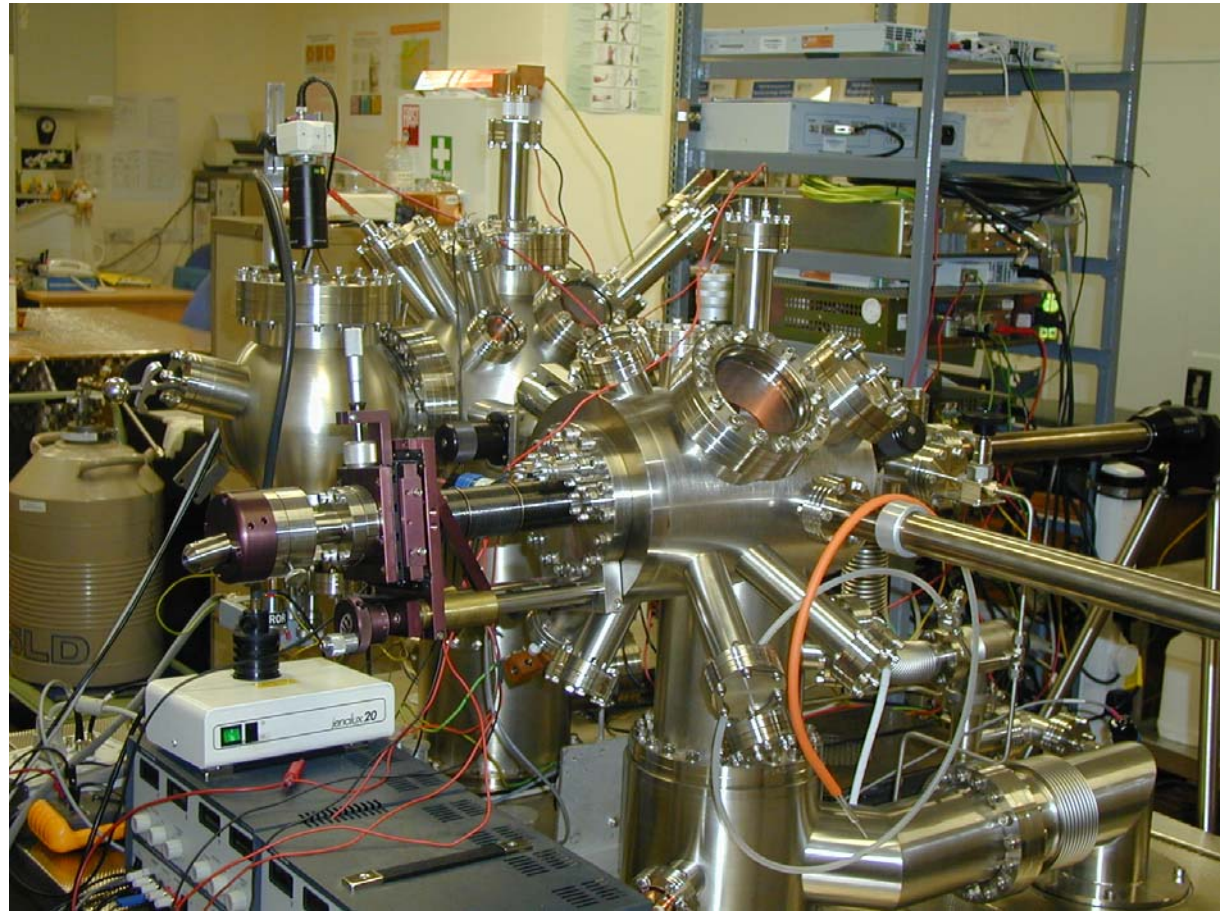
1. Semiconductor quantum dots, nanowires
2. Semimetal (Sb, Bi) nanostructures: thermoelectric
3. Magnetic/spintronic materials: Mn, MnSb,...
4. ...

## Inert Substrates

- HOPG (highly-oriented pyrolytic graphite): easy-to-prepare inert conductive substrate for growing nearly *free-standing* nanostructures, mostly *clusters & compact crystallites*, but *1D or quasi-1D* nanostructures also form sometimes
- Si-based inert surfaces: dielectric layers ( $\text{SiO}_2$ ,  $\text{Si}_3\text{N}_4$ ,  $\text{HfO}_2$ ,  $\text{SrTiO}_3$ ) on Si, close to real applications

# Experimental Facility

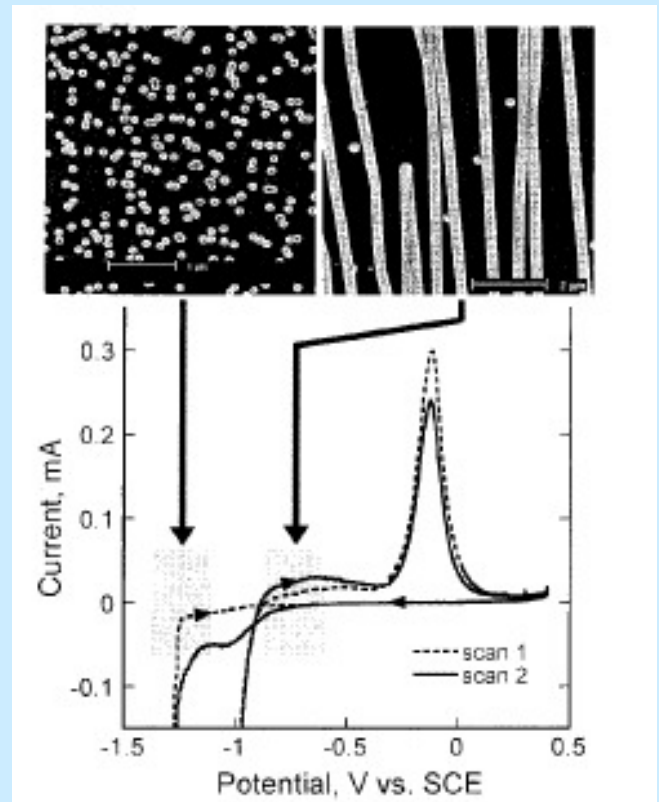
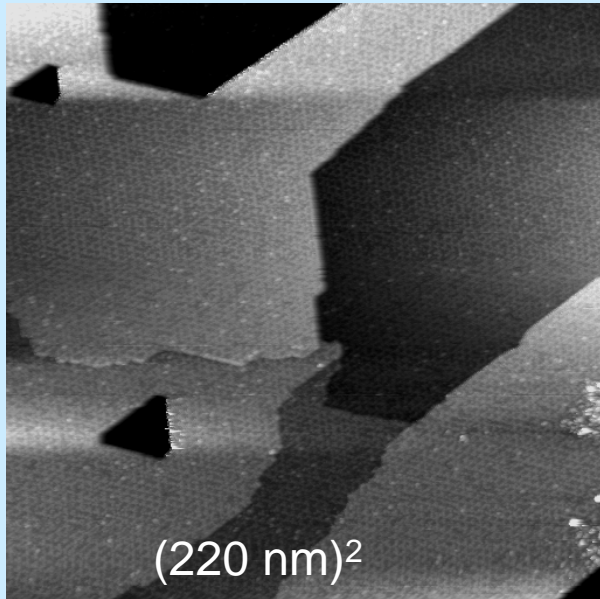
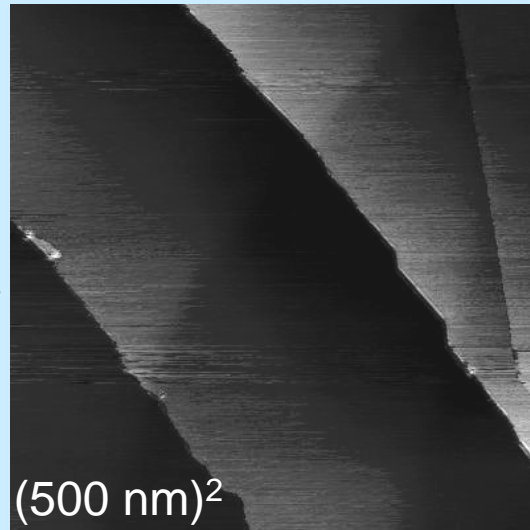
- Sb (mostly  $\text{Sb}_4$ )  
Bi, Mn, Al, Ge  
from thermal  
evaporators
- STM at RT
- Other ex situ  
measurement:  
XPS, AFM,  
SEM, VSM



Omicron UHV STM system

# Substrate Preparation

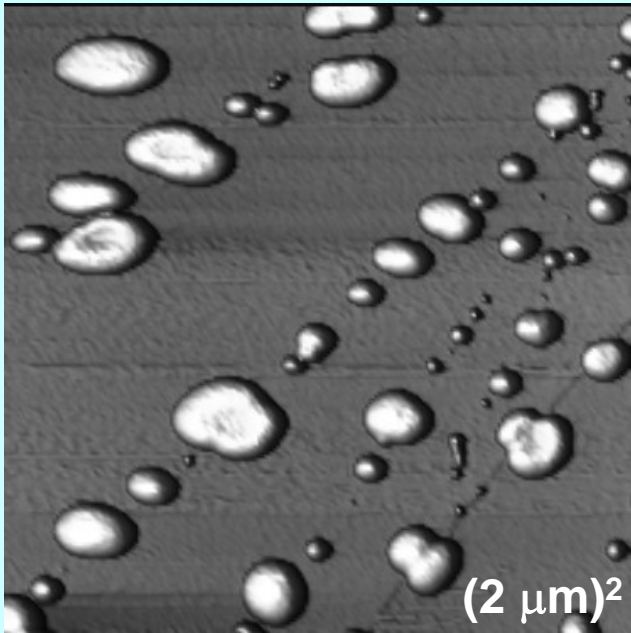
HOPG: Cleave in air, quickly loaded into UHV chamber, degas at  $\sim 500$  °C for hours



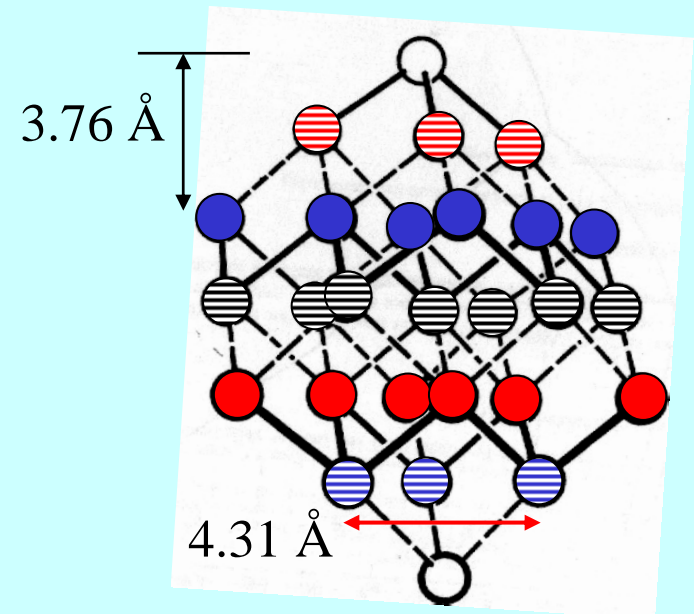
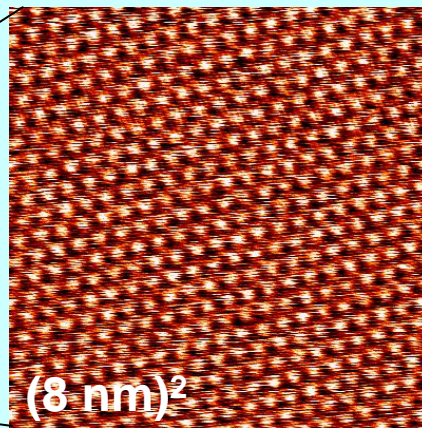
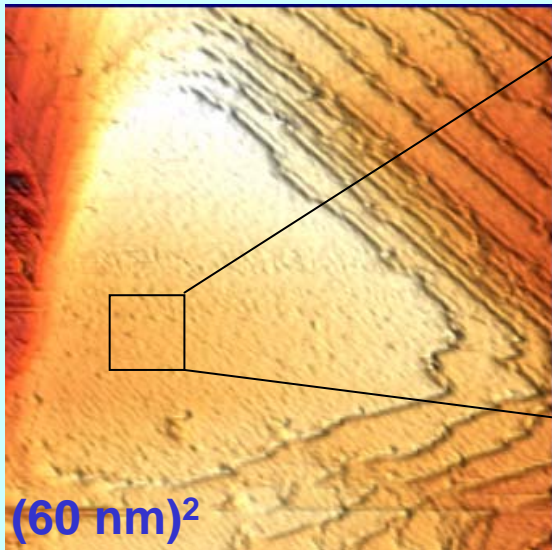
Mo particles and wires on HOPG by electrodeposition  
(Penner, J. Phys. Chem. B 106 (2002) 3339)

SiN<sub>x</sub> on Si(111): obtained by nitridation of Si(111) at  $\sim 900$  °C using NH<sub>3</sub> or NO  
Crystalline SiN<sub>x</sub> of thickness 1-2 nm  
(Wang et al., Surf. Sci. 494 (2001) 83)

# 3D Sb Islands on HOPG

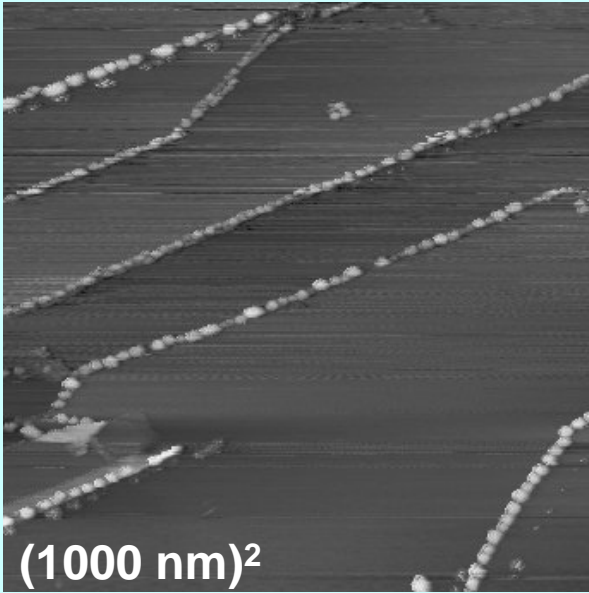


- ◆ Formed after deposition at RT
- ◆ Mostly found along HOPG steps
- ◆ **Extremely easy coarsening**
- ◆ Round surface even at large volume
- ◆ (111) Facets on top of large islands, hexagonal period  $4.24 \pm 0.08 \text{ \AA}$

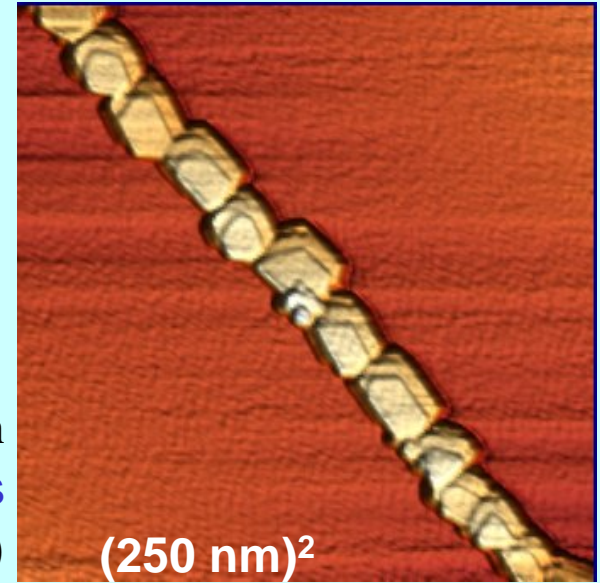


Rhombohedral Sb

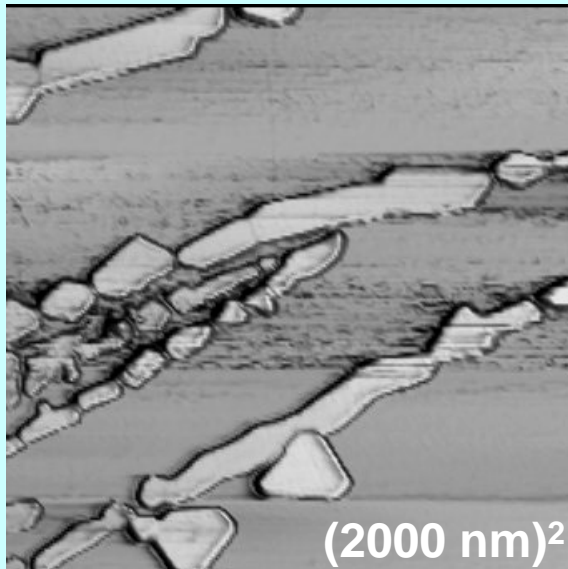
# Al on HOPG: Clusters → crystallite chains → film



3 Å deposited at RT  
Spherical clusters ( $h \sim 4 - 8$  nm) mostly found at HOPG steps

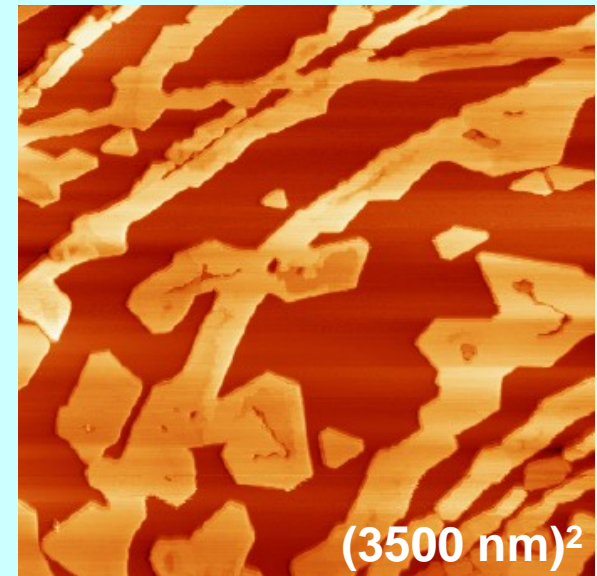


After 8 Å deposition  
Flat crystallites  
( $h \sim 3 - 5.5$  nm)

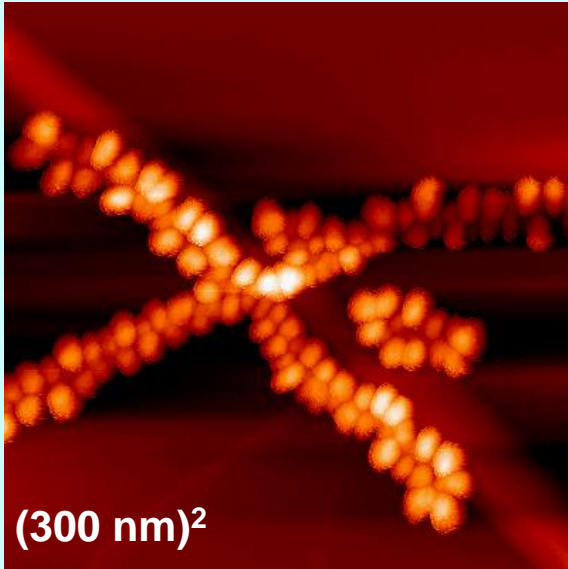


Easy coalescence  
of Al crystallites

further deposition  
gradually leads to a  
continuous film of  
thickness  $\leq 30$  nm

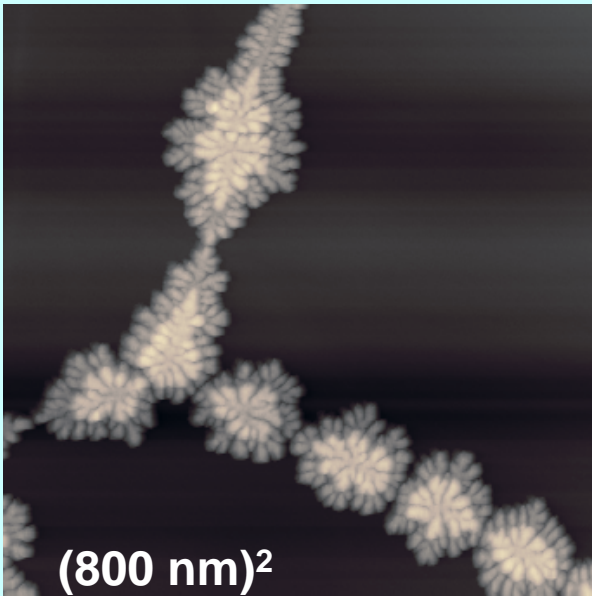
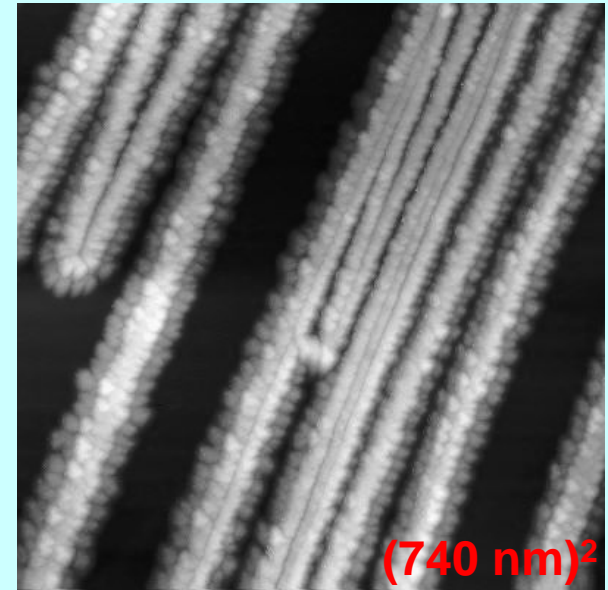


# Ge on HOPG: clusters chains & islands



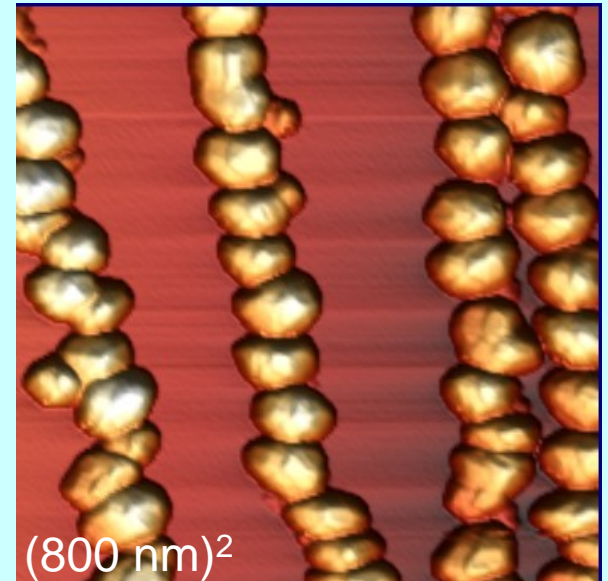
1) Ge cluster at steps and defects, height ~ 9 nm

2) Double-layer cluster chains, **not necessarily along HOPG steps**



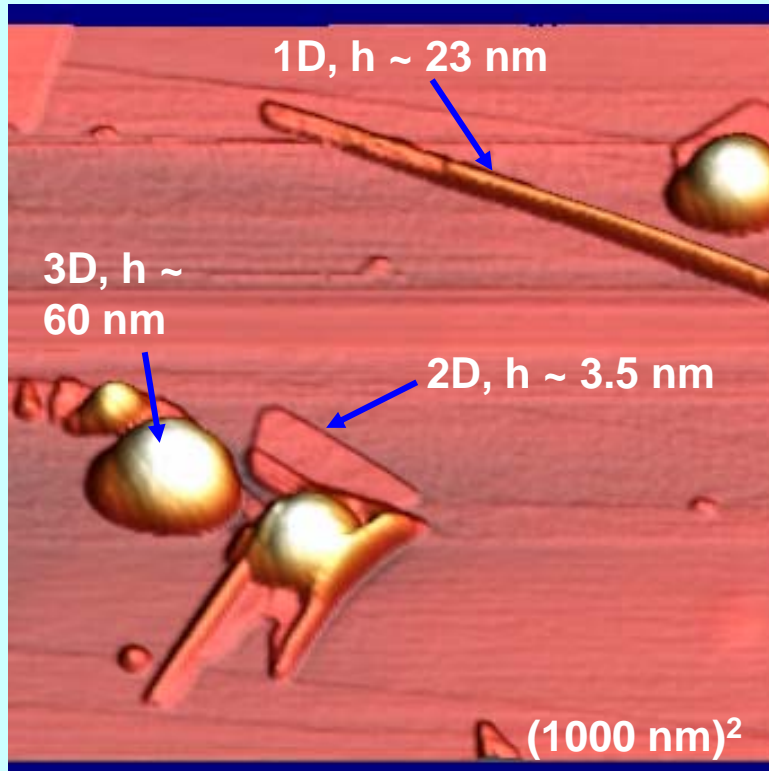
3) Double-layer fractal islands formed at defects & **sub-surface steps**

5 nm Ge deposited at 450 K, **Crystallites** of  $h \sim 45$  nm

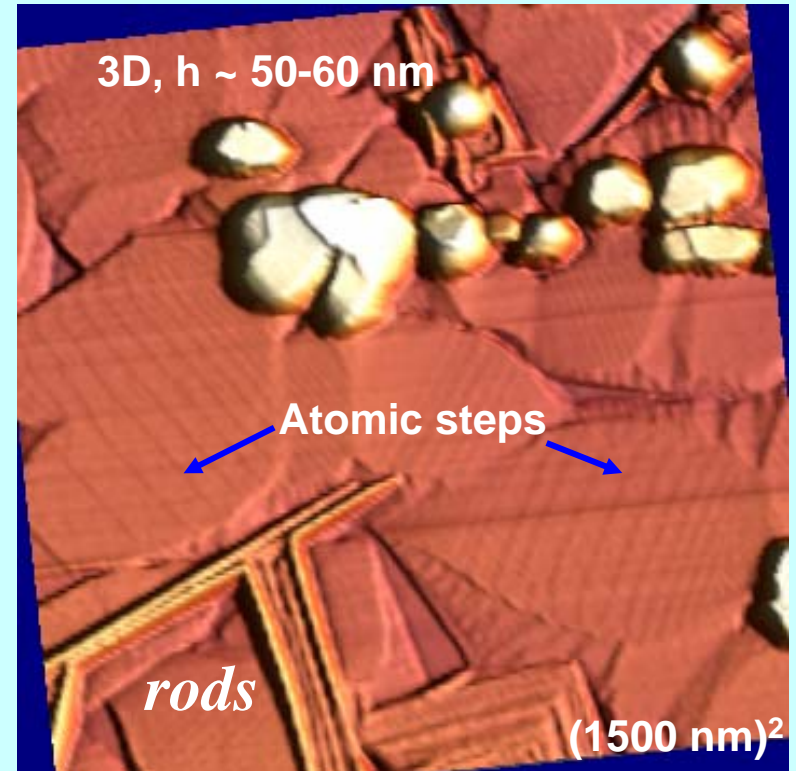




# 2D & 1D Sb Nanostructures on HOPG



$\text{Sb}_4$ ,  $F = 4 \text{ \AA}/\text{min}$ ,  $12 \text{ \AA}$   
deposited at RT. 3D, 2D & 1D  
islands formed in early stage



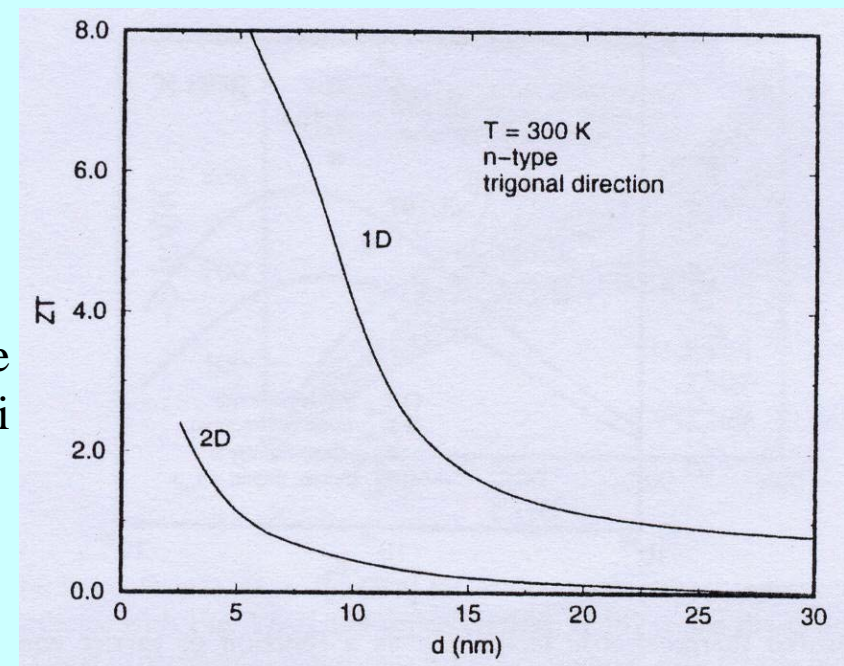
$\text{Sb}_4$ ,  $F = 4 \text{ \AA}/\text{min}$ ,  $100 \text{ \AA}$   
deposited at RT. 3D islands  
“crystallize”, 2D film grows  
dominantly in later stage

# Semimetal (Sb, Bi) Nanostructures

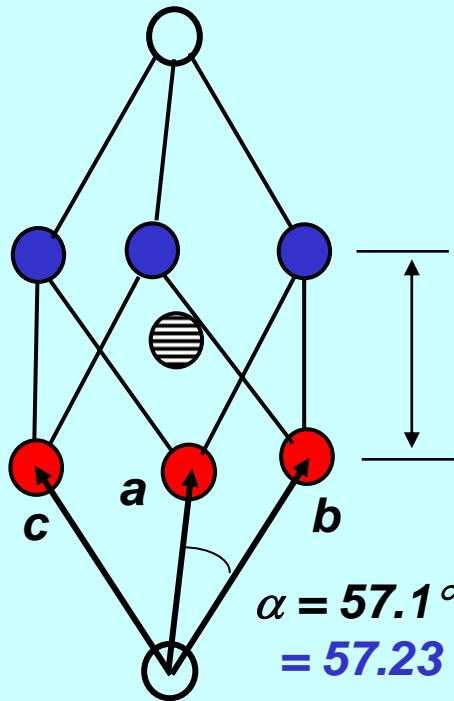
- **Bulk Sb & Bi:** low carrier density ( $\sim 10^{-5}$  of metal), low carrier effective mass, high mobility, long electron de Broglie wavelength ( $\sim 40$  nm), highly effective phonon scattering by heavy ions
- **Low-D Sb & Bi:** easy to show quantum confinement effect, semimetal-to-semiconductor transition
- **Thermoelectric application of low-D Bi &  $\text{Bi}_{1-x}\text{Sb}_x$ :** high efficiency thermoelectric materials

Calculated thermoelectric figure of merit  $ZT$  for low-D Bi

(see: MS Dresselhaus et al, 2001; JP Heremans et al, PRL, 2002; TE Humphrey et al, PRL, 2005)

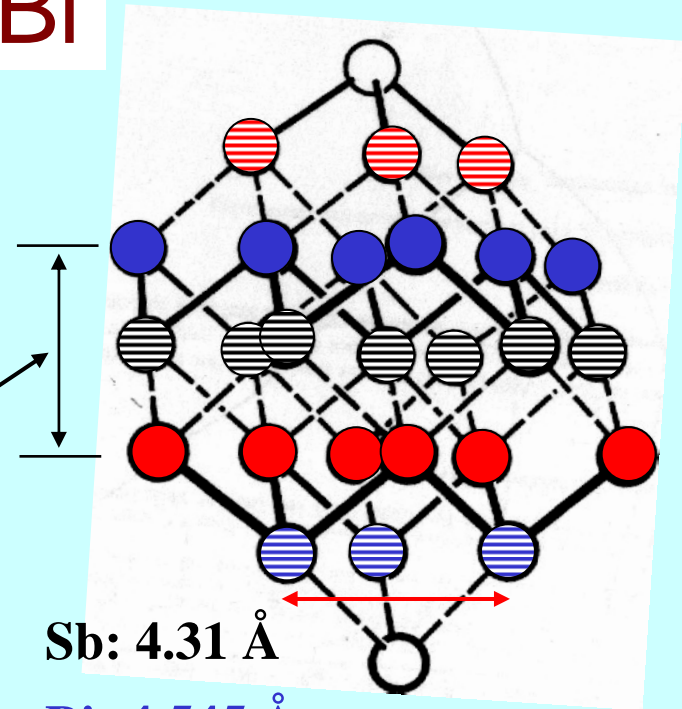


# Lattice Structure of Sb & Bi

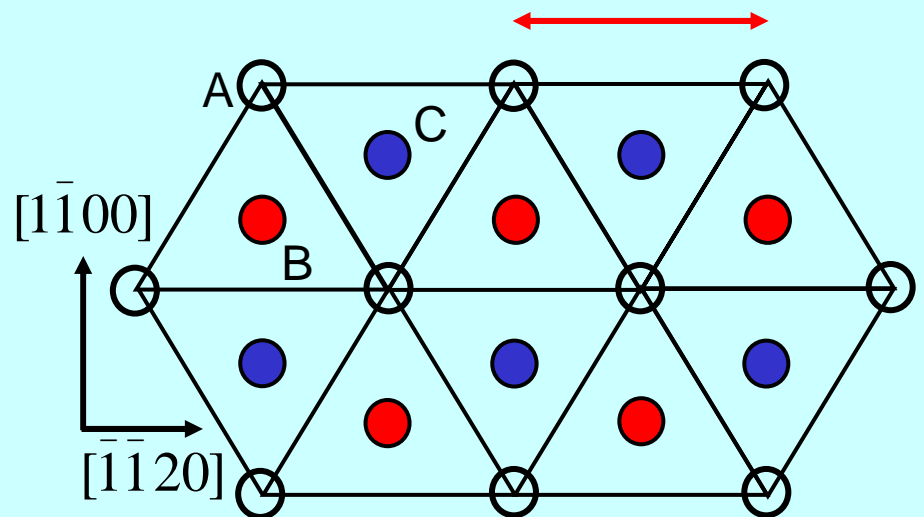


Sb: 3.76 Å

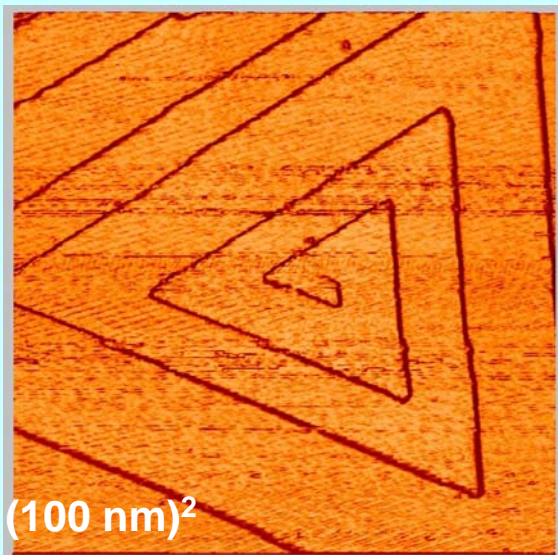
Bi: 3.95 Å



Rhombohedral lattice:  
A distorted cubic lattice



# Sb wetting film on graphite



Steps straight

Unit-layer step  
height:

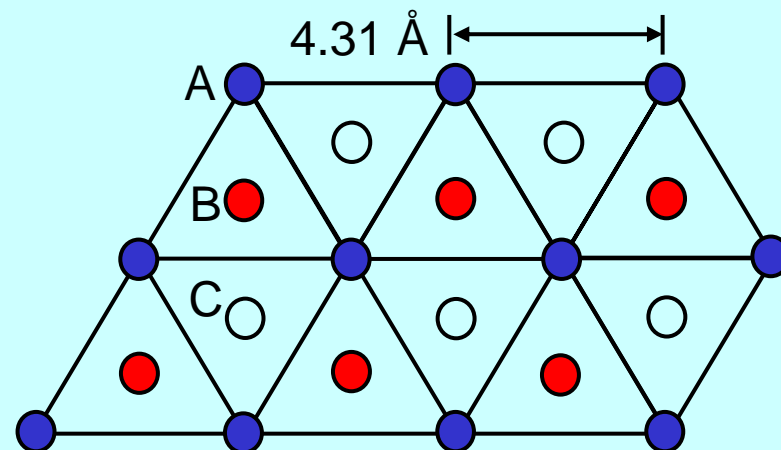
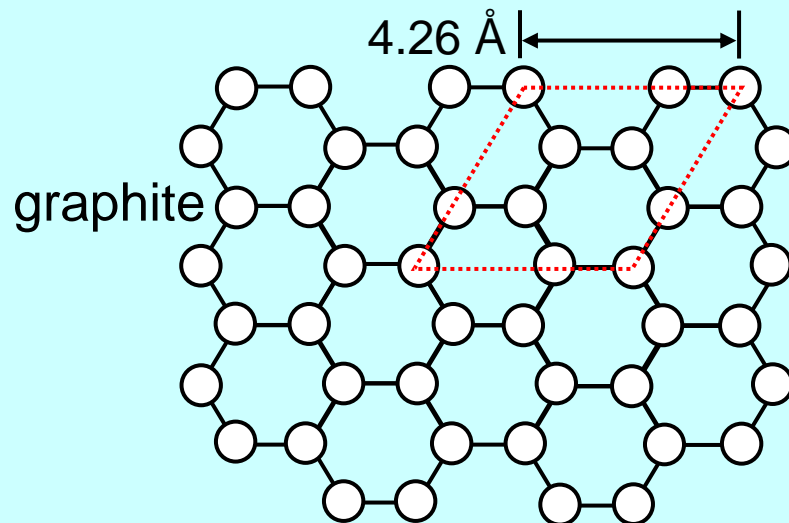
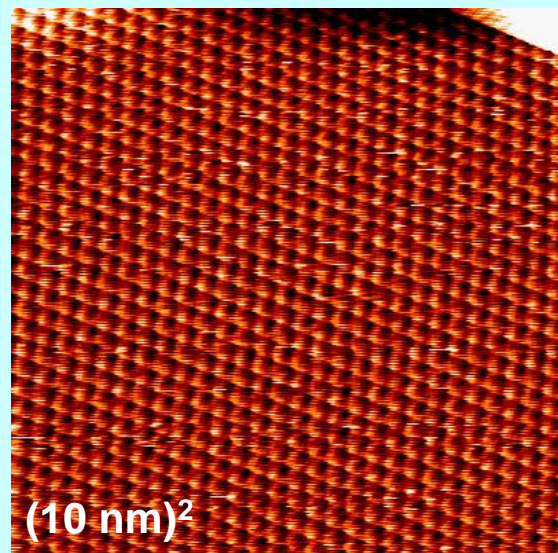
$$h = 3.96 \pm 0.20 \text{ \AA}$$

Lateral period:

$$a = 4.17 \pm 0.06 \text{ \AA}$$

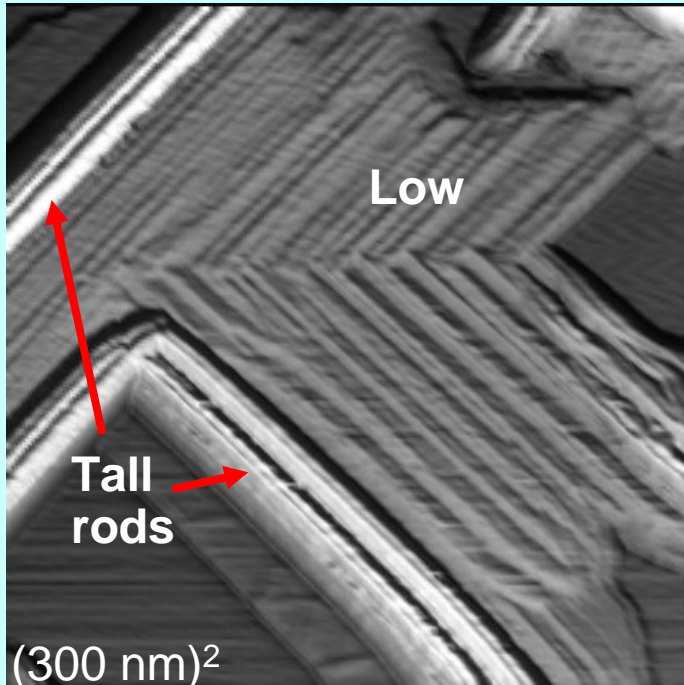
*Shrinking film*

Sb crystalline  
2D films wet  
graphite, but  
not perfectly  
epitaxial

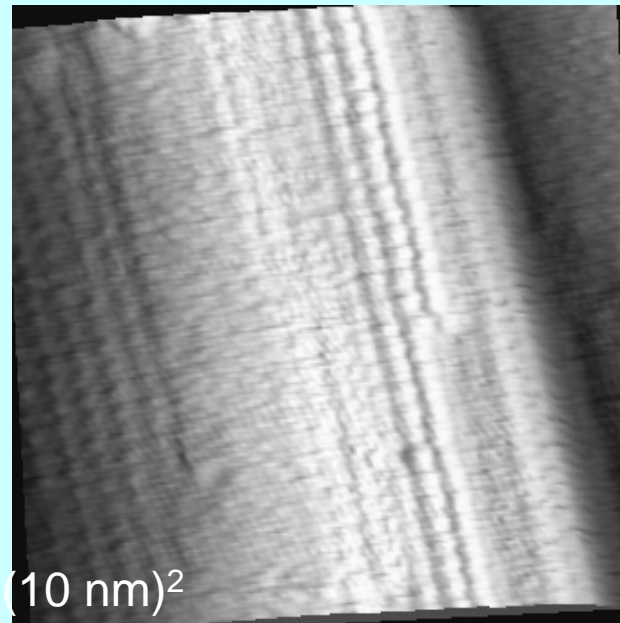


Bulk Sb  $\alpha$ -phase (RHL):  
layer spacing  $h = 3.8 \text{ \AA}$ ,  
lateral period  $a = 4.31 \text{ \AA}$

# Sb Nanowires on HOPG



Tall ( $\geq 20$  nm) & Low ( $\leq 15$  nm) NWs, some in "L" shape



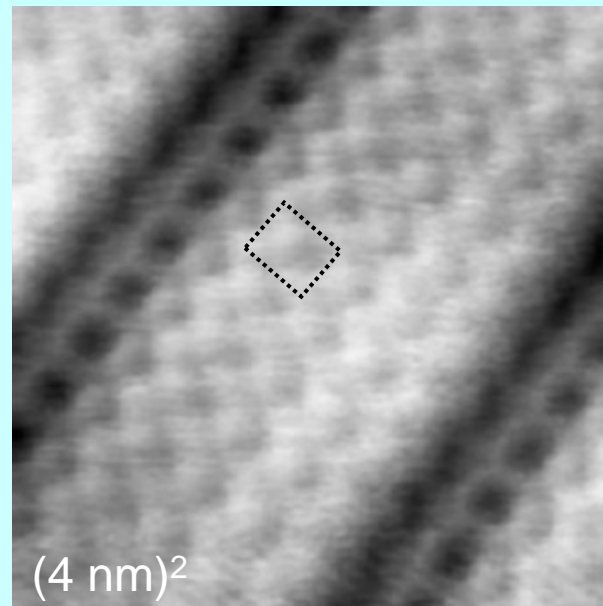
Row structures  
on tall NWs

Row spacing:

$$4.5 \pm 0.2 \text{ \AA}$$

Period along row:

$$3.70 \pm 0.15 \text{ \AA}$$



Lower NWs away  
from corner

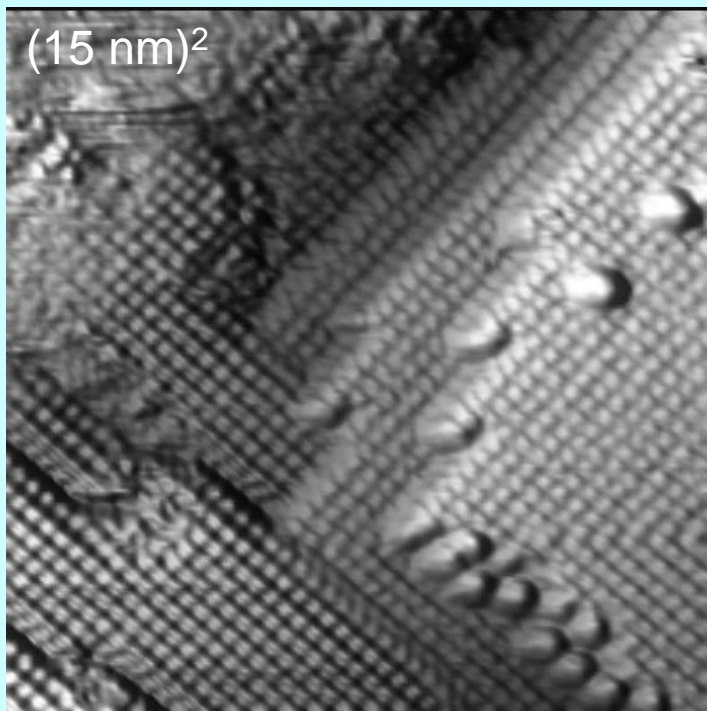
Rectangular cell:

$$(4.40 \pm 0.15 \text{ \AA}) \times$$

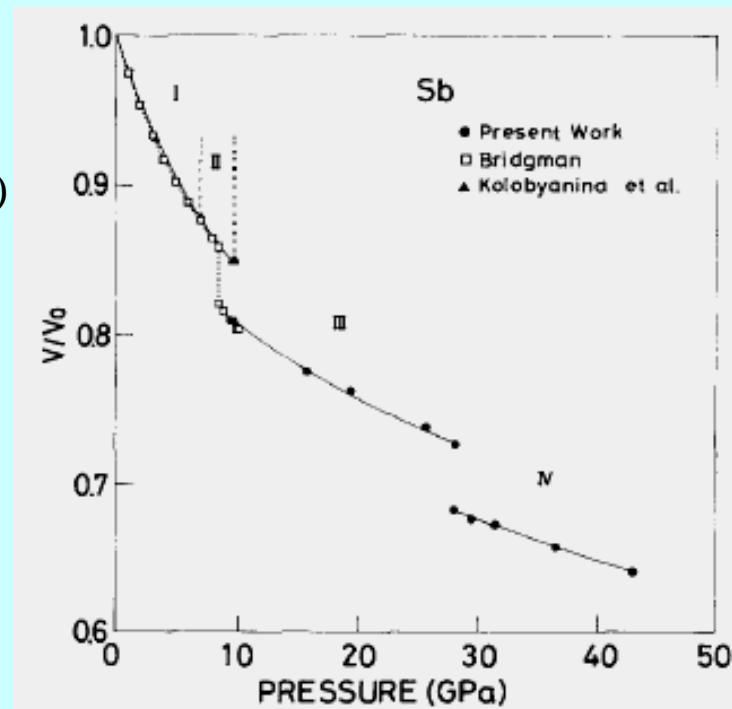
$$(3.93 \pm 0.15 \text{ \AA})$$

# Sb NWs: Simple cubic Sb in compressed state

Sb under increasing pressure:  
RHL → SC → dis. bcc → bcc  
(Aoki *et al.*, Solid State Comm. (1983))



Lower Sb NWs at corner: Square cell of period  $4.18 \pm 0.15 \text{ \AA}$



Sb in SC phase (at  $\sim 7.5 \text{ GPa}$ )

Atomic volume  $V \approx 0.85V_0 = 25.7 \text{ \AA}^3$

Atomic spacing in SC:  $2.95 \text{ \AA}$

Period of  $\sqrt{2} \times \sqrt{2}$  supercell on Sb(100):  $4.17 \text{ \AA}$

# Why are Sb NWs & films in compressive state?

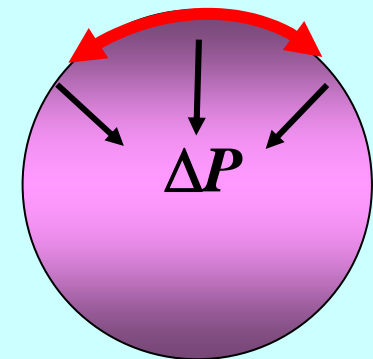
*Surface stress* on nanostructures induces *large* Laplace pressure (Cammara et al, 2000)

In a sphere of radius  $r$ , Laplace pressure:

$$\Delta P = 2\sigma/r$$

For  $\sigma \sim 1$  N/m,  $r \sim 1$  nm,  $\Delta P \sim 2$  GPa

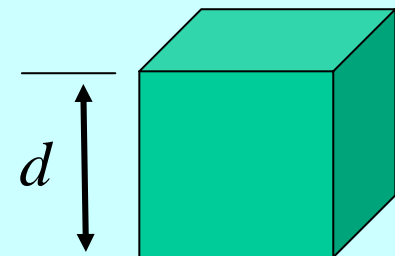
*Surface stress*  $\sigma$



*A nanostructure can be in a strongly compressive state intrinsically, especially in nucleation stage*

Laplace pressure in a cube

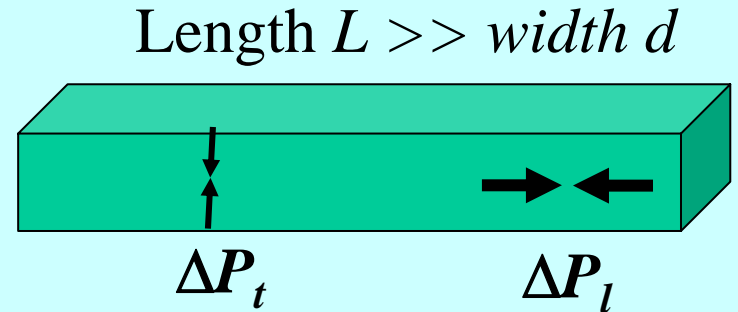
$$\Delta P = 4\sigma/d$$



# Laplace pressure in Sb NWs

Pressure along axis:  $\Delta P_l = 4\sigma/d$

Transverse pressure:  $\Delta P_t = 2\sigma/d$



*In NW, internal longitudinal  $P_{Lap}$  is twice of transverse  $P_{Lap}$*

## Strain in Sb NW (Poisson ratio $\nu \approx 0.3$ )

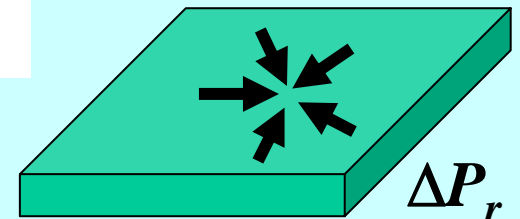
Along NW axis:  $\varepsilon_l = -[\Delta P_l - 2\nu\Delta P_t]/Y = -2.8\sigma/(Yd)$

Transverse to axis:  $\varepsilon_t = -[(1-\nu)\Delta P_t - \nu\Delta P_l]/Y \approx -0.2\sigma/(Yd)$

## In-plane pressure in Sb wetting layer

(Free-standing, thickness  $t$ )

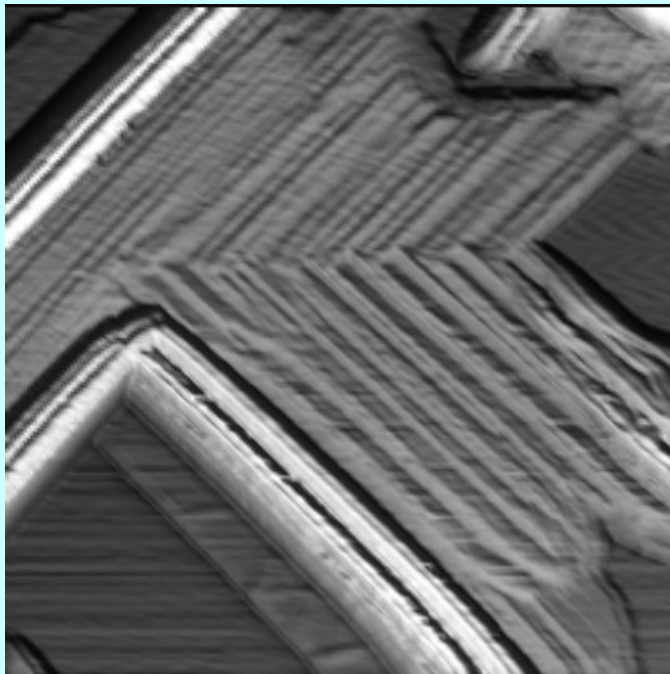
$$\Delta P_r \sim 2\sigma/t$$





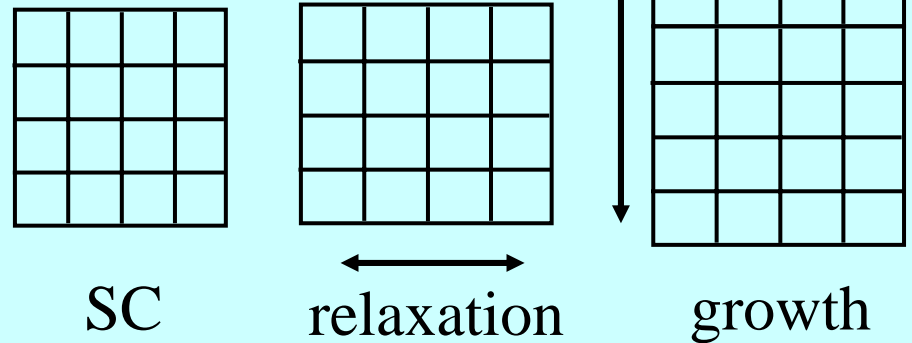
# Sb NW Growth

*symmetry breaking*

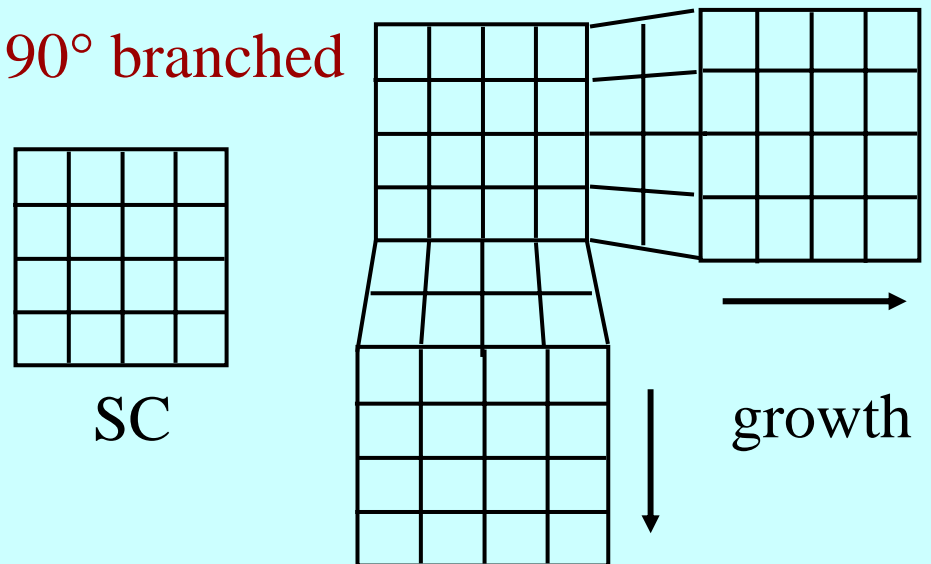


Strain energy is reduced effectively even with stress relief in one direction (Tersoff & Tromp, PRL **1993**).

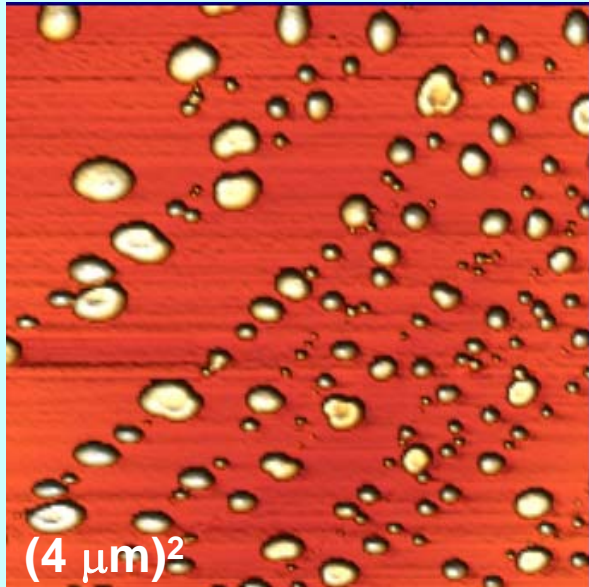
Straight NWs



90° branched



# Selective fabrication of Sb Nanostructures



Low flux (1.8 Å/min) at RT

Little Sb<sub>4</sub> dissociation

**3D islands exclusively**

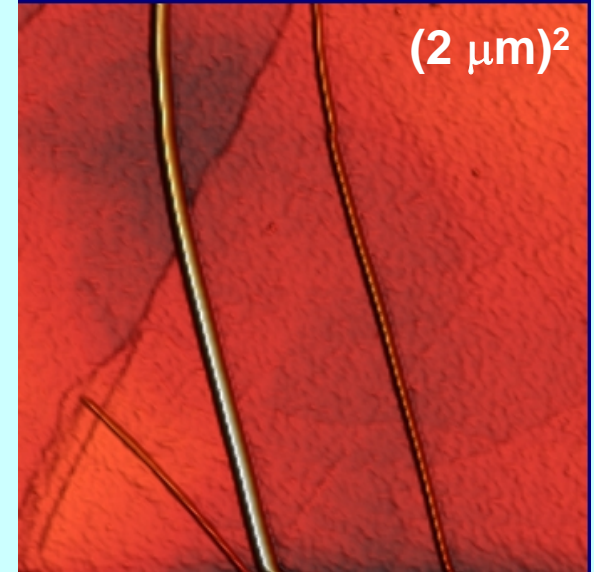


High flux (18 Å/min)

at 100 °C

More Sb<sub>4</sub> dissociation

**3D islands suppressed**



Low flux (3 Å/min)

Diffusion vs dissociation of Sb<sub>4</sub>: play with the rates

# Selective fabrication: Play with the rates of Diffusion & dissociation of $\text{Sb}_4$ on HOPG

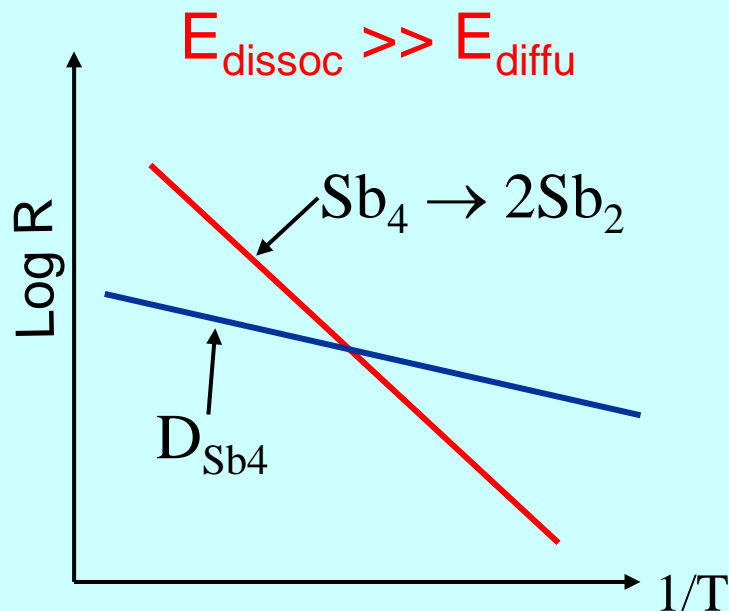
$$E_{\text{diffu}}(\text{Sb}_4) \leq 0.1 \text{ eV}$$

On Si(001):  $E_{\text{dissoc}} = 0.7 \text{ eV}$   
(Mo, PRB 1993)

On HOPG:  $E_{\text{dissoc}} \sim 1 \text{ eV}$

Ratio of dissociation vs diffusion rates:

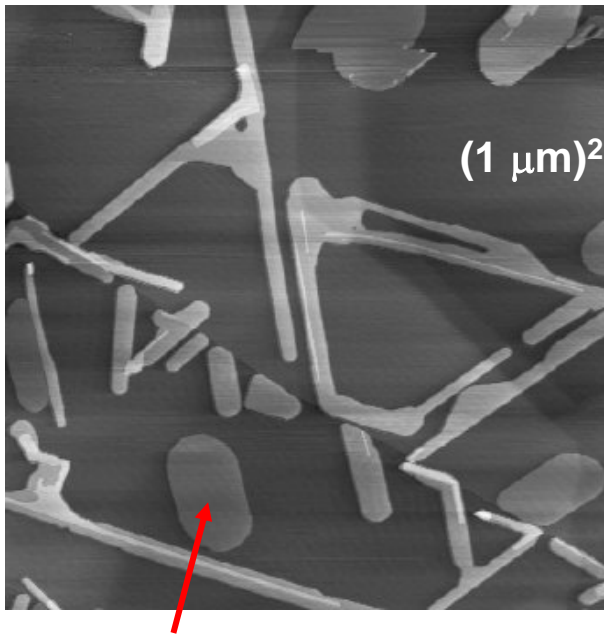
$$\frac{R_{\text{chemisorb}}}{R_{\text{diffusion}}} \propto \exp\left(-\frac{E_c - E_d}{kT}\right)$$



This ratio increases by a factor of  $\geq 300$  as  $T$  changes from  $30^\circ\text{C}$  to  $100^\circ\text{C}$

# Formation of quasi-1D Bi Nanostructures

(Bi evaporator only generates Bi<sub>1</sub> &  
Bi<sub>2</sub>, so no 3D islands form initially)



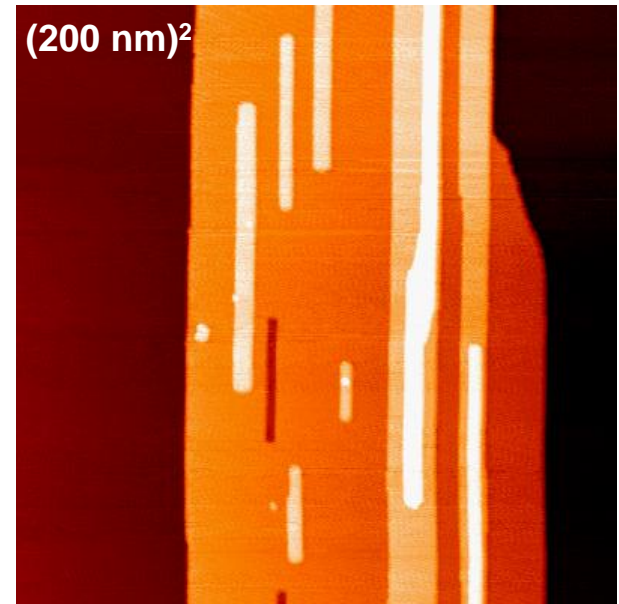
2D islands, height  $\sim 1$  nm

Hexagonal (111) lattice of period:

$4.31 \pm 0.06 \text{ \AA}$  ( $4.55 \text{ \AA}$  in bulk)

*Strongly compressed in-plane*

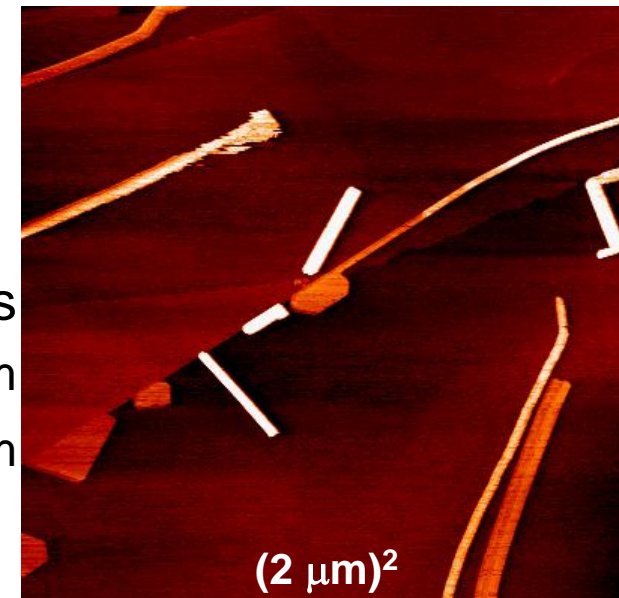
Stripes with  
rectangular lattice:  
 $4.34 \text{ \AA} \times 4.67 \text{ \AA}$   
on bulk Bi(110):  
 $4.55 \text{ \AA} \times 4.75 \text{ \AA}$



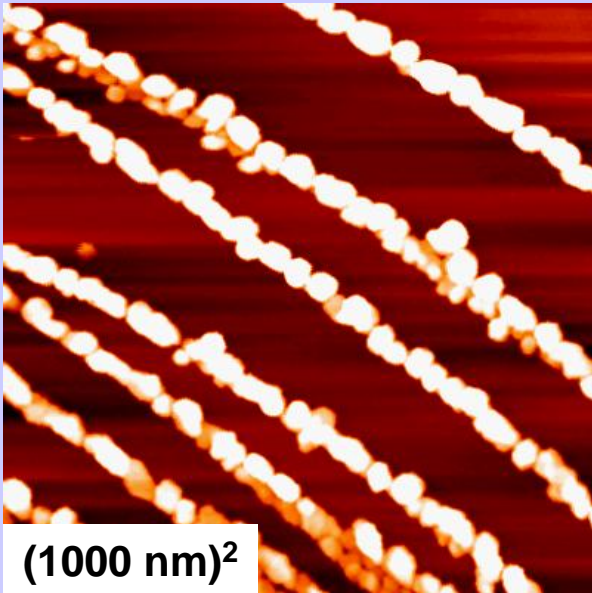
Bi nano-ribbons

Height  $\sim 3$ -25 nm

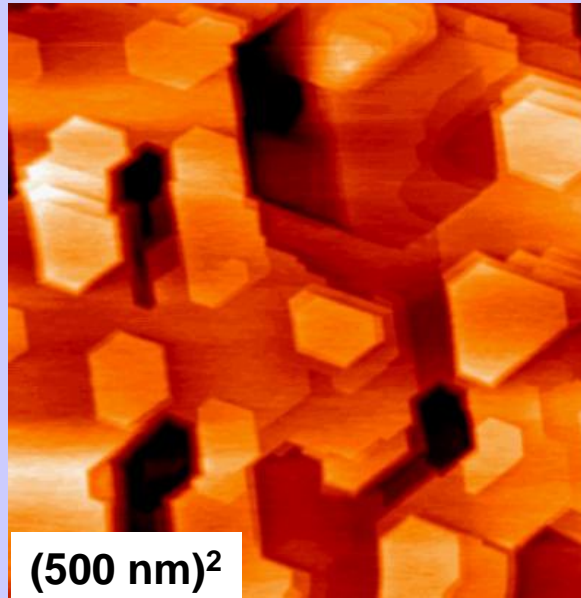
Width  $\sim 25$ -70 nm



# MnSb growth on HOPG

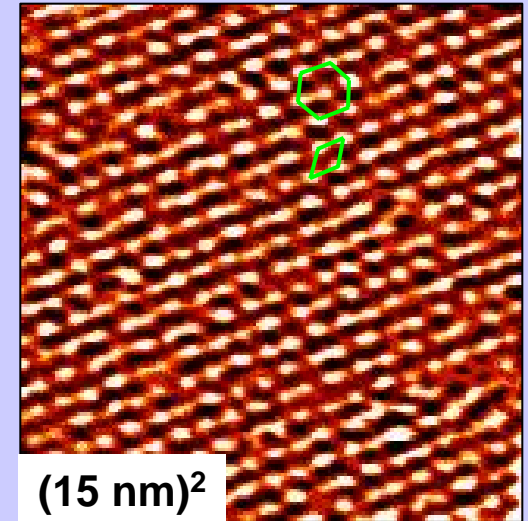


Co-evaporating Mn & Sb at 150° C, MnSb cluster chains along the steps initially, average cluster height ~ 20 nm, lateral size ~ 50nm.



Mostly hexagonal-shaped atomically flat MnSb(0001) terraces, minimum step height  $5.8 \pm 0.2 \text{ \AA}$

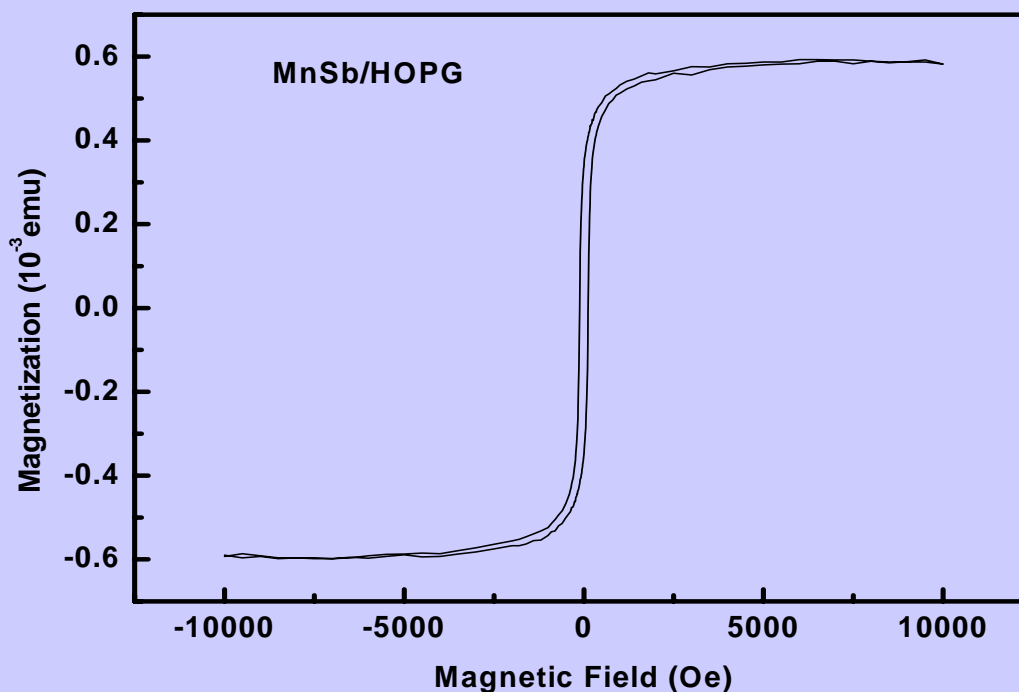
100 nm film



Periodicities 8.3 Å, MnSb(0001)- $2 \times 2$ . Grown in Sb-rich conditions & annealed in Sb flux, surface likely Sb-terminated.

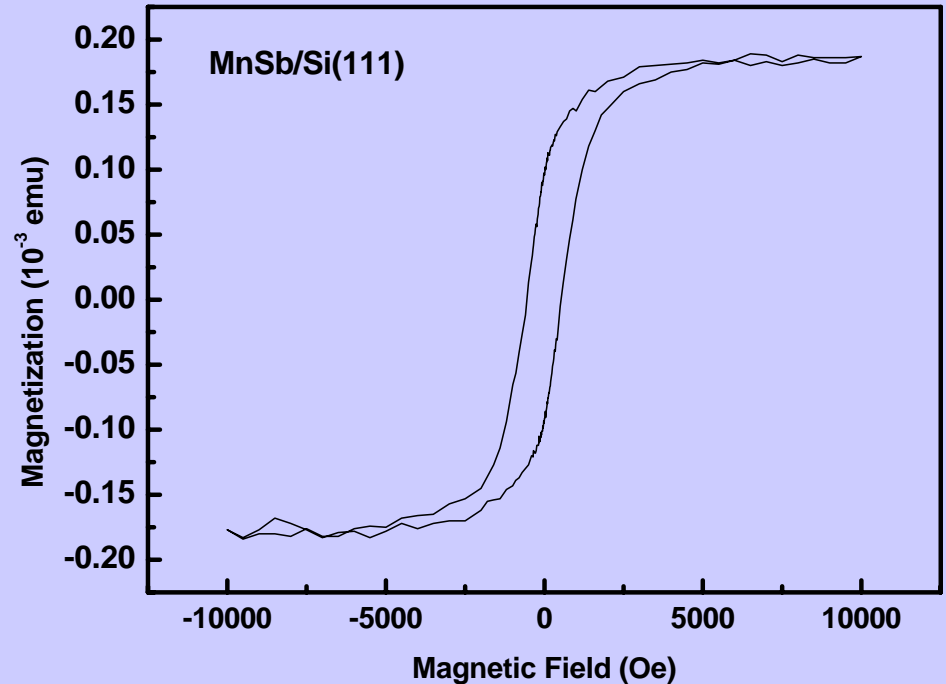
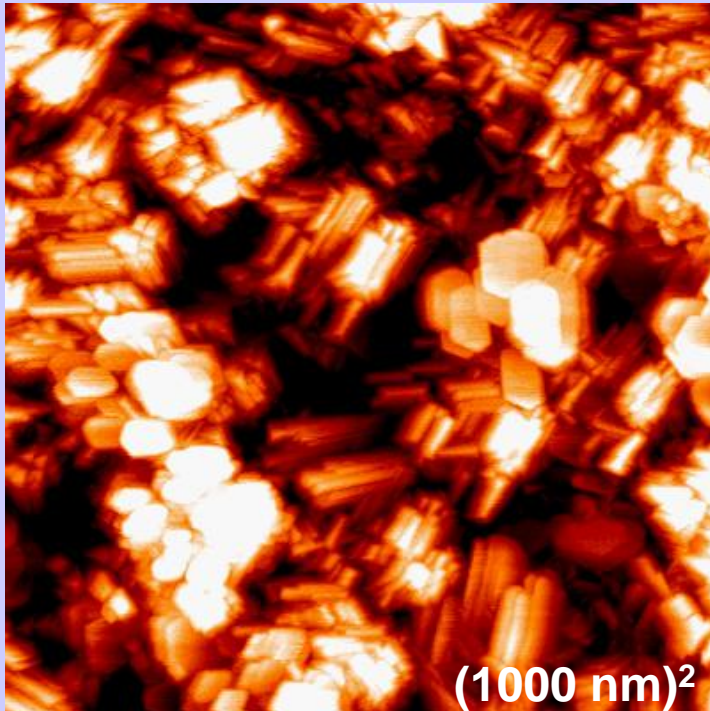
# MnSb: ferromagnetic ( $T_c$ 590 K), nearly half-metallic

## Magnetic measurement using VSM



Hysteresis loop for 100-nm MnSb film on HOPG  
measured at RT with H parallel to film plane.

# MnSb growth on Si(111)

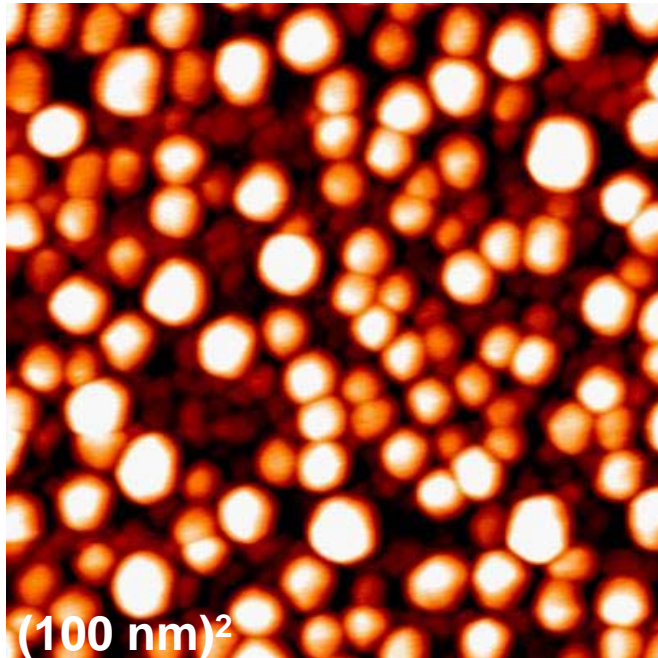


VSM at RT, H in film plane

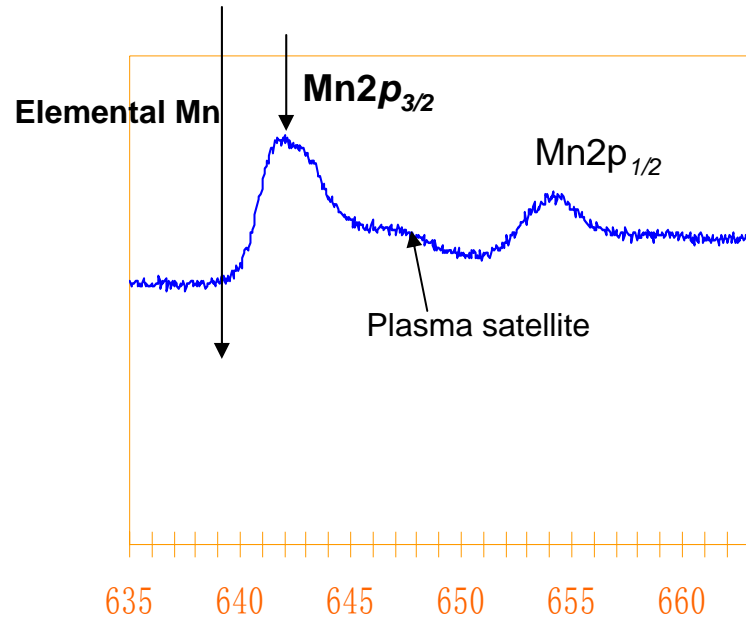
MnSb ( $\sim 30$ nm) grown on Si(111) at  $300^\circ$  C

Some islands in (0001), but other orientations also exist

# MnSb growth on SiN<sub>x</sub>/Si(111)



Grown at 250° C, MnSb nanodots with average diameter of 10nm, hard to grow further to show facets



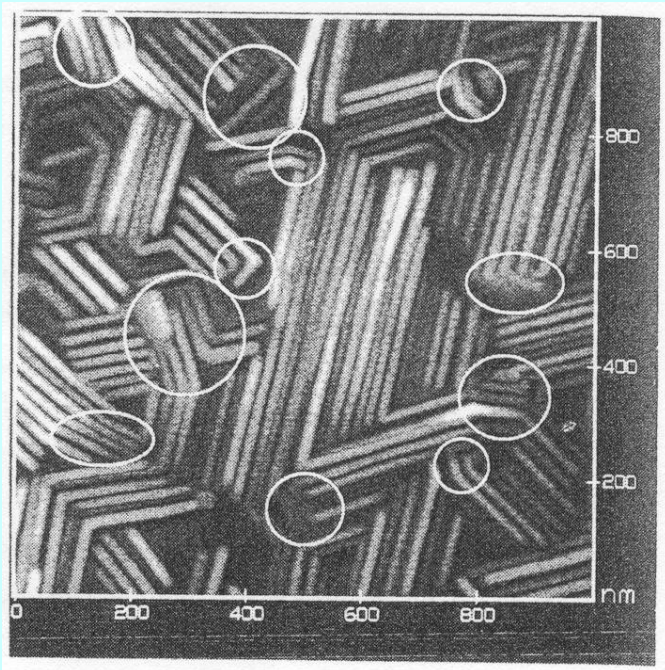
Mn2p XPS, shift ~ 2.5 eV to higher binding E, indicating MnSb compound



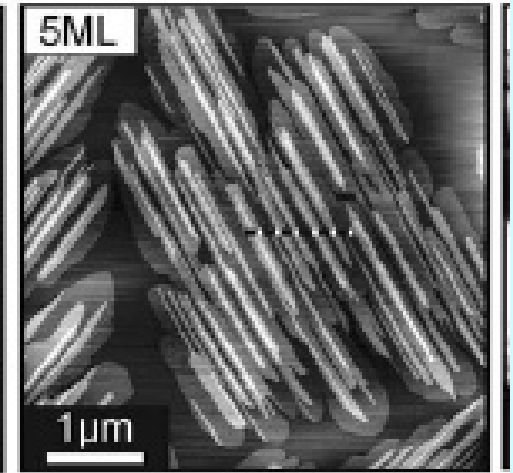
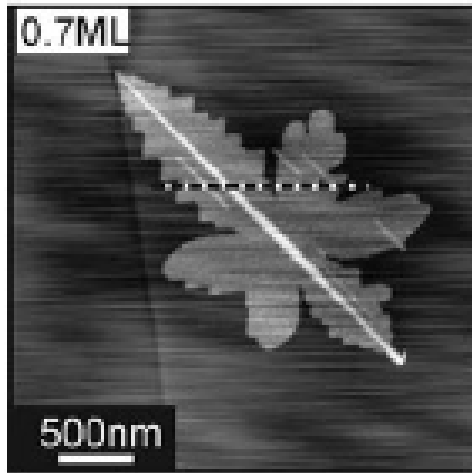
# Summary

- Self-assembled cluster chains of Ge, Al & Mn on HOPG
- 3 types of Sb & Bi nanostructures form on HOPG. 3D & 2D close to RHL, 1D NWs highly compressed.
- Sb & Bi NWs start in a compressive state, due to  $P_{Laplace}$  induced by surface stress on a nanoscale object
- Certain growth selectivity of Sb growth is realized: play with  $Sb_4$  diffusion & dissociation rates
- Ferromagnetic MnSb: more oriented growth on HOPG than on Si(111) or  $SiN_x/Si(111)$
- Bonding nature of Sb, Bi, MnSb on HOPG?

# Bi nanostructures on HOPG



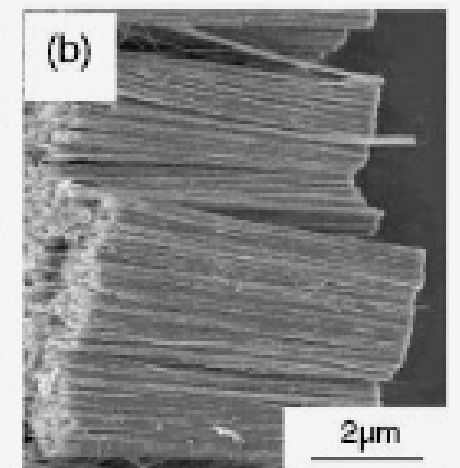
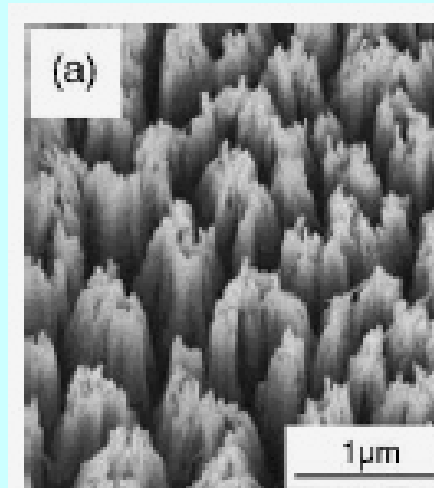
(H. Wang et al, 1993)



(S.A. Scott et al, 2005)

## Bi NW array grown in AAM

(L. Li et al, 2005)



## Different Sb Nanostructures on HOPG

3D island	Rhombohedral (111) Facet $a = 4.27 \pm 0.10 \text{ \AA}$	Formed by diffusion & nucleation of $\text{Sb}_4$ at HOPG steps at low T & low F
2D film	RHL (small distortion) $a = 4.17 \pm 0.10 \text{ \AA}$ $h = 3.96 \pm 0.20 \text{ \AA}$	Formed by chemisorption & dissociation of $\text{Sb}_4$ at high T & high F
1D rod	SC & distorted, $V/V_0 \approx 0.85$ , $\sqrt{2} \times \sqrt{2}$ supercell on Sb(100)	Formed by chemisorption & dissociation of $\text{Sb}_4$ at high T & high F

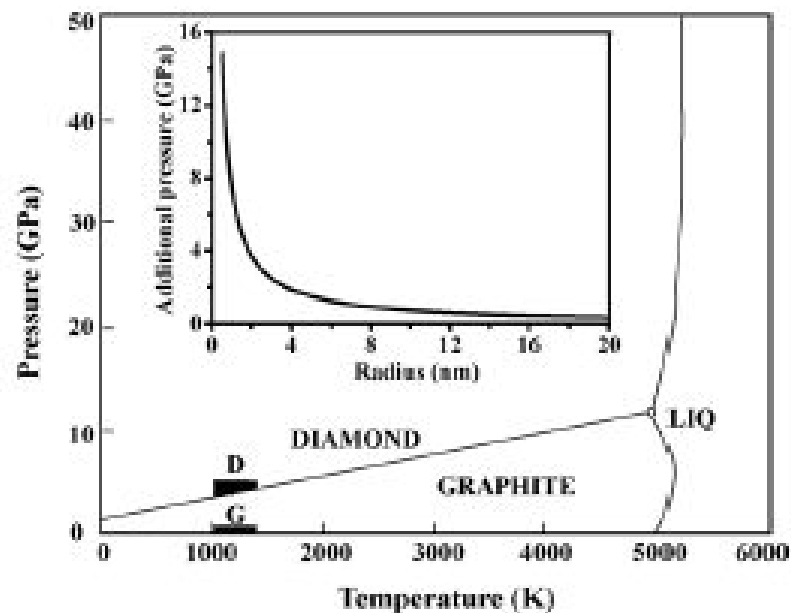
1D rods disappear @ 260° C anneal

2D & 3D islands are stable against annealing to 300° C

## Thermodynamics of metastable phase nucleation at the nanoscale

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## Deformation of Ni particle in CNT growth

(S. Helveg et al., Nature 427 (2004) 426)

